## IN THE CLAIMS:

Please amend the claims as follows:

 (Currently Amended) A laser exposing apparatus having comprising a first laser source emitting a first laser beam;

a second laser source emitting a second laser beam shorter in wavelength than the first laser beam;

optical means for directing the first laser beam and the second laser beam to a photosensitive member; and

adjusting means for <u>selectable</u> adjustment <u>of respective</u> such that the optical path <u>lengths</u> of the <u>first and</u> second laser <u>beams so that the optical path length of the</u> <u>first laser</u> beam <u>is set to be relatively shorter than the optical path length of the second laser</u> <u>beam which is set to be relatively</u> to the photosensitive member becomes longer than that of the first laser beam.

- 2. (Original) A laser exposing apparatus according to Claim 1, wherein the first laser source and the second laser source are provided in a semiconductor chip.
- 3. (Currently Amended) A laser exposing apparatus according to Claim 1, wherein said optical means comprises lenses differing in having refractive index from each other indices that differ depending on wavelength.

4. (Cancelled)

5. (Currently Amended) A laser exposing apparatus according to Claim 2, wherein said adjusting means has a rotating mechanism for rotating the semiconductor chip with substantially the centers of a center between the first laser source and the second laser source as the center of rotation.

Please add Claim 6, as follows:

6. (New) A laser exposing apparatus according to Claim 1, wherein optical paths having shorter and longer optical path lengths from the respective laser sources to the photosensitive member are arranged consecutively, and said adjusting means sets the optical path length to the optical path of the second laser beam.